

PRODUCT/PROCESS CHANGE NOTIFICATION

PCN MMS-MMY/09/4475 Notification Date 04/13/2009

M95512, 512Kbit Serial SPI Bus EEPROM Redesign and Upgrade to the CMOSF8H Process Technology

Table 1. Change Implementation Schedule

Forecasted implementation date for change	06-Apr-2009
Forecasted availabillity date of samples for customer	06-Apr-2009
Forecasted date for STMicroelectronics change Qualification Plan results availability	06-Apr-2009
Estimated date of changed product first shipment	13-Jul-2009

Table 2. Change Identification

Product Identification (Product Family/Commercial Product)	M95512 products family				
Type of change	Waferfab process change				
Reason for change	Line up to state of art of design				
Description of the change	Redesign and Upgrade to the new CMOSF8H Process Technology.				
Product Line(s) and/or Part Number(s)	See attached				
Description of the Qualification Plan	See attached				
Change Product Identification	"K" for the new F8H version				
Manufacturing Location(s)					

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Table 3. List of At	tachments
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Customer Part numbers list	
Qualification Plan results	

Customer Acknowledgement of Receipt	PCN MMS-MMY/09/4475
Please sign and return to STMicroelectronics Sales Office	Notification Date 04/13/2009
□ Qualification Plan Denied	Name:
□ Qualification Plan Approved	Title:
	Company:
□ Change Denied	Date:
□ Change Approved	Signature:
Remark	

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DOCUMENT APPROVAL

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PRODUCT / PROCESS CHANGE NOTIFICATION

M95512, 512Kbit Serial SPI Bus EEPROM Redesign and Upgrade to the CMOSF8H Process Technology

What is the change?

The **M95512**, 512Kbit Serial SPI Bus EEPROM product family, currently produced using the CMOSF8L Process Technology in the ST Rousset (France) 8 inch wafer diffusion plant has been redesigned and will be upgraded to the new **CMOSF8H** Process Technology in the same wafer diffusion plant.

- AC product performance is improved (20MHz at Vcc=5V, 10MHz at Vcc=2.5V, 5MHz at Vcc=1.8V)
- ESD HBM passes 3000V

Upgraded version is functionally backward compatible to previous version, as per datasheet rev.9 dated July 2008.

Why?

The strategy of STMicroelectronics Memory Division is to support our customers on a long-term basis. In line with this commitment, the qualification of the M95512 in the new CMOSF8H Process Technology will increase the production capacity throughput and consequently improve the service to our customers.

Also, the new die is fitting inside the MLP 2x3 package (M95512-RMB6TG).

When?

The production of the upgraded M95512 with the new CMOSF8H will ramp up from middle of April 2009 and shipments can start from middle of July 2009 onward (upon customer approval).

How will the change be qualified?

The new version of the M95512 will be qualified using the standard ST Microelectronics Corporate Procedures for Quality and Reliability.

The Qualification Report QREE0807 will be available Week 18.

What is the impact of the change?

- Form: marking change (see **Device marking** paragraph)
- Fit: no change
- Function: change on AC performances and ESD HBM

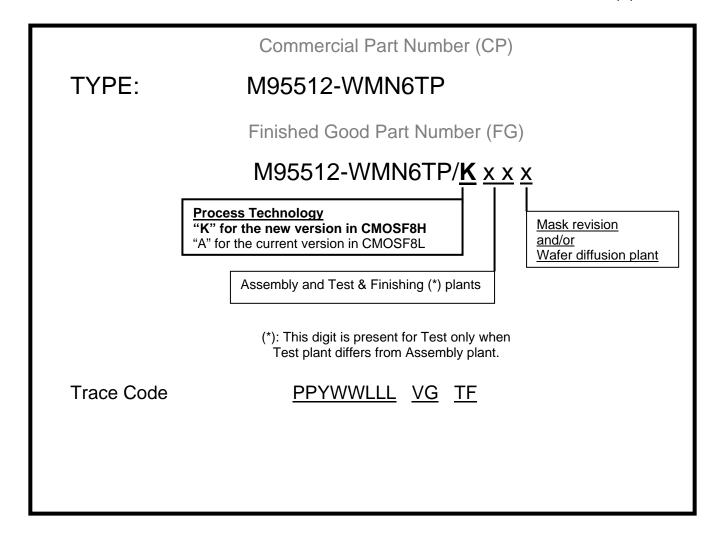
How can the change be seen?

BOX LABEL MARKING

On the BOX LABEL MARKING, the difference is visible inside the **Finished Good Part Number**: the **Process Technology** identifier is "**K**" for the **upgraded version**, this identifier being "A" for the current version.

→ Example for M95512-WMN6TP (2.5V to 5.5V Vcc range, SO8N RoHS* compliant package)

*RoHS: Restriction of the use of certain Hazardous Substances in electrical and electronic equipments



How can the change be seen?

- DEVICE MARKING

On the DEVICE MARKING of the **SO8N** package, the difference is visible inside the trace code (PYWWT) where the last digit "T" for **Process Technology** identifier is "**K**" for the **upgraded version** in **CMOSF8H**, the identifier being "B" for the current version in CMOSF8L.

Upgraded M95512 in CMOSF8H Current M95512 in CMOSF8L

SO8N

Example: M95512-WMN6TP

95512WP PYWW**K** 95512WP PYWW**B**

The traceability for each device is as follows:

PYWWT

P = Assembly plant

Y = Last digit of the Year of Assembly

WW = Assembly Week code

T = Process Technology code/ Wafer Fab ID

For **TSSOP8**, the difference is visible inside the product name: **upgraded version** in **CMOSF8H** is ending by "**K**", the current version was ending by "P".

Upgraded M95512 n CMOSF8H

in CMOSF8H 512WK Current M95512 in CMOSF8L

TSSOP8

Example: M95512-WDW6TP

512W**K** PYWW 512W**P** PYWW

The traceability for each device is as follows:

P Y WW

P = Assembly plant

Y = Last digit of the Year of Assembly

WW = Assembly Week code

M95512, 512Kbit Serial SPI Bus EEPROM Redesign and Upgrade to the CMOSF8H Process Technology

Appendix A- Product Change Information

Product family / Commercial products:	M95512 products family
Customer(s):	All
Type of change:	Wafer fab Process Technology change
Reason for the change:	Line up to state of art of design.
Description of the change:	Redesign and Upgrade to the new CMOSF8H Process Technology.
Forecast date of the change:	Week 15 / 2009
Forecast date of Qualification samples availability for customer(s):	M95512-WDW6TP → Available M95512-WMN6TP → Available M95512-RMN6TP → Week 18 M95512-RDW6TP → Week 19
Forecast date for the internal STMicroelectronics change, Qualification Report availability:	Week 18 / 2009
Marking to identify the changed product:	Process and fab ID see marking above
Description of the qualification program:	Standard ST Microelectronics Corporate Procedures for Quality and Reliability
Product Line(s) and/or Part Number(s):	M95512-RDW6TP M95512-RMN6TP M95512-WDW6TP M95512-WMN6TP
Manufacturing location:	Rousset 8 inch wafer fab
Estimated date of first shipment:	Week 29 / 2009

Appendix B: Intermediate Qualification Report:



QREE0807 Intermediate qualification report

New design / M95512 using the CMOSF8H technology in the Rousset 8" Fab

Table 1. Product information

Table 1. Product Information					
General information					
Commercial product	M95512-RMN6TP M95512-WMN6TP M95512-RDW6TP M95512-WDW6TP M95512-RMB6TG				
Product description	512 Kbit serial SPI bus EEPROM with high-speed clock				
Product group	MMS				
Product division	MMY - Memory				
Silicon process technology	CMOSF8H				
Wafer fabrication location	RS8F - ST Rousset 8*, France				
Electrical Wafer Sort test plant location	ST Rousset, France				

Table 2. Package description

Package description	Assembly plant location	Final test plant location	
SOBN	ST Shenzhen, China	ST Shenzhen, China	
30014	Amkor P1, Philippines	Amkor P3, Philippines	
TSSOP8	ST Shenzhen, China	ST Shenzhen, China	
100000	Amkor P1, Philippines	Amkor P3, Philippines	
UFDFPN8 (MLP8) 2 x 3 mm	Amkor P3, Philippines	Amkor P3, Philippines	

Reliability / Qualification assessment: 504 hrs PASS on 2 lots - Pending reliability results 1008 hrs

Note: This document will remain a draft until the product is qualified.

25 March 2009 Rev 1 1/10

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Reliability evaluation overview

QREE0807

1 Reliability evaluation overview

1.1 Objectives

This qualification report summarizes the results of the reliability trials that were performed to qualify the new design M95512 using the CMOSF8H silicon process technology in the ST Rousset 8" diffusion fab.

The voltage and temperature ranges covered by this document are:

- 2.5 to 5.5 V at -40 to 85 °C for M95512-W devices
- 1.8 to 5.5 V at -40 to 85 °C for M95512-R devices

The CMOSF8H is a new advanced silicon process technology in the ST Rousset 8" fab, with Double Poly and Double Metal process. This document serves for the qualification of the named product and the named silicon process technology in the named diffusion fab.

1.2 Conclusion

The new design M95512 using the CMOSF8H silicon process technology in the ST Rousset 8" diffusion tab has passed all ESD and latch-up requirements. Product validation and reliability trials are ongoing.

Refer to Section 3: Reliability test results for details.



QREE0807 Device characteristics

2 Device characteristics

Device description

This electrically erasable programmable memory (EEPROM) device is accessed by a high-speed SPI-compatible bus. The memory array is organized as 65536 x 8 bits.

The device is accessed by a simple serial interface that is SPI-compatible. The bus signals are C, D and Q.

The device is selected when Chip Select (\overline{S}) is taken low. Communications with the device can be interrupted using Hold (HOLD).

Refer to the product datasheet for more details.



Reliability test results QREE0807

3 Reliability test results

This section contains a general description of the reliability evaluation strategy.

The named products are qualified using the standard STMicroelectronics corporate procedures for quality and reliability.

The product vehicle used for the die qualification is presented in Table 3.

Table 3. Product vehicles used for die qualification

Product	Silicon process technology			Assembly plant location
M95512	CMOSF8H	ST Rousset 8"	CDIP8	Engi assy (1)

^{1.} CDIP8 is a ceramic package used only for die-oriented reliability trials.

The product vehicle and silicon process technologies used for package qualification are presented in *Table 4*.

Table 4. Product vehicles used for package qualification

Product	Silicon process technology	Wafer fabrication location	Package description	Assembly plant location	
			SO8N	ST Shenzhen	
M95512 CMOSF8H	ST Rousset 8"	30014	Amkor P1		
		TSSOP8	ST Shenzhen		
		1550F6	Amkor P1		
		X	UFDFPN8 (MLP8) 2 x 3 mm	Amkor P3	

3.1 Reliability test plan and result summary

The reliability test plan and the result summary are presented as follows:

- in Table 5 for die-oriented tests
- in Table 6 for TSSOP8 Shenzhen package-oriented tests
- Reliability tests on all other packages are planned, but results are not yet available.

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QREE0807 Reliability test results

Table 5. Die-oriented reliability test plan and result summary (CDIP8 / Engineering package)⁽¹⁾

	Test short description							
Test			Cample	/ of	Duration	Results fail / sample size		
	Method	Conditions	Sample size / lots			M95512		
						Lot 1	Lot 2	Lot 3
	High temperature	e operating life after endurance						
	AEC-Q100-005	1 Million E/W cycles at 25 °C then:	80	3 .	504 hrs	0/80	0/80	Results W17'09
EDR -	720-0100-000	HTOL 150 °C, 6 V	00		1008 hrs	Results W15'09	Results W15'09	Results W21'09
	Data retention af	ter endurance						
	1 1 2	1 Million E/W cycles at 25 °C then:	80	3 .	504 hrs	0/80	0/80	Results W17'09
	ALG-2100-003	HTSL at 150 °C	80		1008 hrs	Results W15'09	Results W15'09	Results W21'09
	Low temperature	operating life						
LTOL	JESD22-A108	-40 °C, 6 ∨	80	3	504 hrs	0/80	0/80	Results W17'09
					1008 hrs	Results W15'09	Results W15'09	Results W21'09
	High temperature storage life							
HTSL	AEC-Q100-005 JESD22-A103	Retention bake at 200 °C	80	3 .	504 hrs	0/80	0/80	Results W17'09
		neterition bake at 200 °C			1008 hrs	Results W15'09	Results W15'09	Results W21'09
	Program/erase endurance cycling + bake							
WEB	Internal spec.	1 Million E/W cycles at 25 °C then: Retention bake at 200 °C / 48 hours	80	3	1 Million cycles / 48 hrs	0/80	0/80	0/80
ESD .	Electrostatic disc	harge (human body model)						
HBM	AEC-Q100-002 JESD22-A114	C = 100 pF, R= 1500 Ω	27	3	N/A	Pass > 3000 V	Pass > 3000 V	Pass > 3000 V
ESD .	Electrostatic discharge (machine model)							
MM	AEC-Q100-003 JESD22-A115	C = 200 pF, R = 0 Ω	6	3	N/A	Pass > 300 V	Pass > 300 V	Results W15'09
	Latch-up (current injection and overvoltage stress)							
LU '	AEC-Q100-004 JESD78A	At maximum operating temperature (150 °C)	6	3	N/A	Class II Level A	Class II Level A	Results W15'09

^{1.} See Table 7: List of terms for a definition of abbreviations.



Reliability test results QREE0807

Table 6. Package-oriented reliability test plan and result summary (TSSOP8 / Shenzhen) (1)

s. Раскаде	-oriented reliability test pia				(155010	7 SHEIIZH	enj	
	Test	short des	cription	on				
	Conditions	Sample size / lots	No. of lots	Duration	Results fail / sample size			
Method					M95512			
					Lot1	Lot2	Lot3	
Preconditioning: moisture sensitivity level 1								
JESD22-A113 J-STD-020D	MSL1, peak temperature at 260 °C, 3 IReflow	345	3	N/A	0/345	0/345	0/345	
Temperature hu	midity bias							
AEC-Q100- JESD22-A101	85 °C, 85% RH, bias 5.5 V	80	3	1008 hrs	0/80	0/80	0/90	
Temperature cy	cling		7/					
AEC-Q100- JESD22-A104	-65 °C / +150 °C	80	3	1000 cycles	0/80	0/80	0/90	
Thermal shocks	1				7			
JESD22-A106	-55 °C / +125 °C	25	3	200 shocks	0/80	0/80	0/90	
Autoclave (pres	sure pot)							
AEC-Q100- JESD22-A102	121 °C, 100% RH at 2 ATM	80	3	168 hrs	0/80	0/80	0/90	
High temperatur	re storage life							
AEC-Q100- JESD22-A103	Retention bake at 150 °C	80	3	1008 hrs	0/80	0/80	0/90	
Early life failure	rate							
AEC-Q100- 008	HTOL 150 °C, 6 V	800	3	48 hrs	Results W24'09	Results W24'09	Results W24'09	
Electrostatic dis	charge (charge device model)							
AEC-Q100- JESD22-C101	Field induced charging method	18	1	N/A	Pass >1500 V	-	-	
	Preconditioning JESD22-A113 J-STD-020D Temperature hu AEC-Q100- JESD22-A101 Temperature cy AEC-Q100- JESD22-A104 Thermal shocks JESD22-A106 Autoclave (pres AEC-Q100- JESD22-A102 High temperatur AEC-Q100- JESD22-A103 Early life failure AEC-Q100- 008 Electrostatic dis AEC-Q100-	Method Conditions Preconditioning: moisture sensitivity level 1 JESD22-A113 J-STD-020D MSL1, peak temperature at 260 °C, 3 IReflow Temperature humidity bias AEC-Q100- JESD22-A101 85 °C, 85% RH, bias 5.5 V Temperature cycling AEC-Q100- JESD22-A104 -65 °C / +150 °C Thermal shocks JESD22-A106 -55 °C / +125 °C Autoclave (pressure pot) AEC-Q100- JESD22-A102 121 °C, 100% RH at 2 ATM High temperature storage life AEC-Q100- JESD22-A103 Retention bake at 150 °C Early life failure rate AEC-Q100- 008 HTOL 150 °C, 6 V Electrostatic discharge (charge device model) AEC-Q100- Field induced charging	Method Conditions Sample size / lots Preconditioning: moisture sensitivity level 1 JESD22-A113 J-STD-020D MSL1, peak temperature at 260 °C, 3 IReflow 345 Temperature humidity bias AEC-Q100-JESD22-A101 85 °C, 85% RH, bias 5.5 V 80 Temperature cycling AEC-Q100-JESD22-A104 -65 °C / +150 °C 80 Thermal shocks JESD22-A106 -55 °C / +125 °C 25 Autoclave (pressure pot) AEC-Q100-JESD22-A102 121 °C, 100% RH at 2 ATM 80 High temperature storage life AEC-Q100-JESD22-A103 Retention bake at 150 °C 80 Early life failure rate AEC-Q100-008 HTOL 150 °C, 6 V 800 Electrostatic discharge (charge device model) AEC-Q100-Field induced charging 48	Method Conditions Sample size / lots No. size / of lots Preconditioning: moisture sensitivity level 1 JESD22-A113 MSL1, peak temperature at 260 °C, 3 IReflow 345 3 Temperature humidity bias AEC-Q100- JESD22-A101 85 °C, 85% RH, bias 5.5 V 80 3 Temperature cycling AEC-Q100- JESD22-A104 -65 °C / +150 °C 80 3 Thermal shocks JESD22-A106 -55 °C / +125 °C 25 3 Autoclave (pressure pot) AEC-Q100- JESD22-A102 121 °C, 100% RH at 2 ATM 80 3 High temperature storage life AEC-Q100- JESD22-A103 Retention bake at 150 °C 80 3 Early life failure rate AEC-Q100- 008 HTOL 150 °C, 6 V 800 3 Electrostatic discharge (charge device model) AEC-Q100- Field induced charging 40 4	Method Conditions size / lots of lots Duration Preconditioning: moisture sensitivity level 1 JESD22-A113 J-STD-020D MSL1, peak temperature at 260 °C, 3 iReflow 345 3 N/A Temperature humidity bias AEC-Q100- JESD22-A101 85 °C, 85% RH, bias 5.5 V 80 3 1008 hrs Temperature cycling AEC-Q100- JESD22-A104 -65 °C / +150 °C 80 3 1000 cycles Thermal shocks JESD22-A106 -55 °C / +125 °C 25 3 200 shocks Autoclave (pressure pot) AEC-Q100- JESD22-A102 121 °C, 100% RH at 2 ATM 80 3 168 hrs High temperature storage life AEC-Q100- JESD22-A103 Retention bake at 150 °C 80 3 1008 hrs Early life failure rate AEC-Q100- 008 HTOL 150 °C, 6 V 800 3 48 hrs Electrostatic discharge (charge device model)	Method Conditions	Method Conditions	

See Table 7: List of terms for a definition of abbreviations.

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^{2.} THB-, TC-, TMSK-, AC- and HTSL- dedicated parts are first subject to preconditioning flow.

Applicable and reference documents

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4 Applicable and reference documents

- AEC-Q100: Stress test qualification for integrated circuits
- SOP 2.6.10: General product qualification procedure
- SOP 2.6.11: Program management fro product qualification
- SOP 2.6.12: Design criteria for product qualification
- SOP 2.6.14: Reliability requirements for product qualification
- SOP 2.6.19: Process maturity level
- SOP 2.6.2: Process qualification and transfer management
- SOP 2.6.20: New process / New product qualification
- SOP 2.6.7: Product maturity level
- SOP 2.6.9: Package and process maturity management in Back End
- SOP 2.7.5: Automotive products definition and status
- JESD22-A101: Steady state temperature humidity bias life test
- JESD22-A102: Accelerated moisture resistance unbiased autoclave
- JESD22-A103: High temperature storage life
- JESD22-A104: Temperature cycling
- JESD22-A106: Thermal shock
- JESD22-A108: Temperature, bias, and operating life
- JESD22-A113: Preconditioning of nonhermetic surface mount devices prior to reliability testing
- JESD22-A114: electrostatic discharge (ESD) sensitivity testing human body model (HBM)
- JESD22-A115: Electrostatic discharge (ESD) sensitivity testing machine model (MM)
- JESD78A: IC Latch-up test
- J-STD-020D: Moisture/reflow sensitivity classification for nonhermetic solid state surface mount devices



Glossary QREE0807

5 Glossary

Table 7. List of terms

Terms	Description	
EDR	NVM endurance, data retention and operational life	
HTOL	High temperature operating life	
LTOL	Low temperature operating life	
нтв	High temperature bake	
WEB	Program/Erase endurance cycling + bake	
ESD HBM	Electrostatic discharge (human body model)	
ESD MM	Electrostatic discharge (machine model)	
LU	Latch-up	
PC	Preconditioning (solder simulation)	
ТНВ	Temperature humidity bias	
тс	Temperature cycling	
TMSK	Thermal shocks	
AC	Autoclave (pressure pot)	
HTSL	High temperature storage life	
ELFR	Early life failure rate	
ESD CDM	Electrostatic discharge (charge device model)	

M95512, 512Kbit Serial SPI Bus EEPROM Redesign and Upgrade to the CMOSF8H Process Technology

Document Revision History					
Date	Rev.	Description of the Revision			
Apr. 06, 2009	1.00	First draft creation			
<u>-</u>					

Source Documents & Reference Documents						
Source document Title		Rev.:	Date:			

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